CLAIMS

1 1. An integrated circuit fabricate	d t	ricated	fabric	circuit	An integrated	An	1.	1
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- forming a first dielectric layer in a manner that varies in the Z-dimension; and
- forming a first conductive layer over the first dielectric layer, the first conductive
- 4 layer also varying in the Z-dimension, the first conductive layer having a length and a
- 5 width, the length being substantially greater than the width, the first conductive layer
- 6 being arranged in a substantially straight line along the X-dimension, and the first
- 7 conductive layer comprising upper segments and lower segments, the upper segments
- 8 being longer than the lower segments.
- 1 2. The integrated circuit recited in claim 1 wherein, in forming the first dielectric
- 2 layer, the first dielectric layer is arranged in a stepped manner.
- 1 3. The integrated circuit recited in claim 1 wherein, in forming the first dielectric
- 2 layer, the first dielectric layer is arranged in an undulating manner.
- 1 4. The integrated circuit recited in claim 1 wherein, in forming the first dielectric
- 2 layer, the first dielectric layer is arranged in a manner that alternates between trenches
- 3 and pedestals.

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- 5. An integrated circuit as recited in claim 1 and further fabricated by:
- forming a second dielectric layer in a manner that varies in the Z-dimension;
- forming a second conductive layer over the second dielectric layer, the second
- 4 conductive layer also varying in the Z-dimension, the second conductive layer having a
- 5 length and a width, the length being substantially greater than the width, the second
- 6 conductive layer being arranged in a substantially straight line along the X-dimension,
- 7 and the second conductive layer comprising upper segments and lower segments, the
- 8 upper segments being longer than the lower segments; and
- 9 coupling the second conductive layer to the first conductive layer.

- 1 6. The integrated circuit recited in claim 5 wherein, in forming the second
- 2 conductive layer, the upper segments in the first conductive layer are offset 180 degrees
- 3 from the upper segments in the second conductive layer.
- 1 7. The integrated circuit recited in claim 1 wherein, in forming the first conductive
- 2 layer, the first conductive layer comprises material from the group consisting of copper,
- 3 aluminum, tungsten, molybdenum, titanium, gold, silver, palladium, a metal silicide,
- 4 doped polysilicon, or is an alloy whose constituents are from the group.
- 1 8. The integrated circuit recited in claim 1 wherein, in forming the first conductive
- 2 layer, the first conductive layer comprises magnetic material.
- 1 9. The integrated circuit recited in claim 8 wherein, in forming the first conductive
- 2 layer, the magnetic material is from the group consisting of nickel-iron, cobalt-
- 3 zirconium-tantalum, iron-tantalum-nickel, nickel-iron-rhenium, and ferro-silicon.
- 1 10. The integrated circuit recited in claim 8 wherein, in forming the first conductive
- 2 layer, the magnetic material is from the group consisting of iron, nickel, cobalt.
- 3 manganese, zinc, zirconium, tantalum, rhenium, silicon, and the rare earth elements, or is
- 4 an alloy whose constituents are from the group.
- 1 11. An integrated circuit package fabricated by:
- 2 forming at least one multi-level inductive element on a substrate in a serpentine
- 3 pattern comprising at least two rows, wherein each row comprises upper conductive
- 4 segments and lower conductive segments, and in at least one row the upper conductive
- 5 segments are longer than the lower conductive segments; and
- 6 mounting an integrated circuit on the substrate.

- 1 12. The integrated circuit package recited in claim 11 wherein, in forming, the upper
- 2 conductive segments and the lower conductive segments are arranged in a stepped
- 3 manner.
- 1 13. The integrated circuit package recited in claim 11 wherein, in forming, the upper
- 2 conductive segments and the lower conductive segments are arranged in an undulating
- 3 manner.
- 1 14. The integrated circuit package recited in claim 11 wherein, in forming, the upper
- 2 conductive segments in one row are offset 180 degrees from the upper conductive
- 3 segments in an adjacent row.
- 1 15. The integrated circuit package recited in claim 11 wherein, in forming, the at
- 2 least one multi-level inductive element comprises at least one layer of magnetic material.
- 1 16. An integrated circuit component fabricated by:
- 2 forming a substrate; and
- forming at least one multi-level inductive element on the substrate in a serpentine
- 4 pattern comprising at least two rows, wherein each row comprises upper conductive
- 5 segments and lower conductive segments, and in at least one row the upper conductive
- 6 segments are longer than the lower conductive segments.
- 1 17. The integrated circuit component recited in claim 16 wherein, in forming the
- 2 substrate, the substrate is formed of material from the group consisting of silicon,
- 3 germanium, gallium arsenide, polyimide, organic material, a printed circuit board, glass,
- 4 quartz, and ceramic.
- 1 18. The integrated circuit component recited in claim 16 wherein, in forming the at
- 2 least one multi-level inductive element, the upper conductive segments and the lower
- 3 conductive segments are arranged in a stepped manner.

- 1 19. The integrated circuit component recited in claim 16 wherein, in forming the at
- 2 least one multi-level inductive element, the upper conductive segments and the lower
- 3 conductive segments are arranged in an undulating manner.
- 1 20. The integrated circuit component recited in claim 16 wherein, in forming the at
- 2 least one multi-level inductive element, the upper conductive segments in one row are
- 3 offset 180 degrees from the upper conductive segments in an adjacent row.
- 1 21. The integrated circuit component recited in claim 16 wherein, in forming the at
- 2 least one multi-level inductive element, the at least one multi-level inductive element
- 3 comprises at least one layer of magnetic material.
- 1 22. An integrated circuit package fabricated by:
- 2 forming a substrate;
- forming at least one multi-level inductive element on the substrate in a serpentine
- 4 pattern comprising at least two rows, wherein each row comprises upper conductive
- 5 segments and lower conductive segments, and in at least one row the upper conductive
- 6 segments are longer than the lower conductive segments; and
- 7 mounting an integrated circuit on the substrate.
- 1 23. The integrated circuit package recited in claim 22 wherein, in forming the
- 2 substrate, the substrate is formed of material from the group consisting of silicon,
- 3 germanium, gallium arsenide, polyimide, organic material, a printed circuit board, glass,
- 4 quartz, and ceramic.
- 1 24. The integrated circuit package recited in claim 22 wherein, in forming the at least
- 2 one multi-level inductive element, the upper conductive segments and the lower
- 3 conductive segments are arranged in a stepped manner.

- 1 25. The integrated circuit package recited in claim 22 wherein, in forming the at least
- 2 one multi-level inductive element, the upper conductive segments and the lower
- 3 conductive segments are arranged in an undulating manner.
- 1 26. The integrated circuit package recited in claim 22 wherein, in forming the at least
- 2 one multi-level inductive element, the upper conductive segments in one row are offset
- 3 180 degrees from the upper conductive segments in an adjacent row.
- 1 27. The integrated circuit package recited in claim 22 wherein, in forming the at least
- 2 one multi-level inductive element, the at least one multi-level inductive element
- 3 comprises at least one layer of magnetic material.
- 1 28. An integrated circuit component fabricated by:
- 2 forming a silicon substrate; and
- forming at least one multi-level inductive element on the substrate in a serpentine
- 4 pattern comprising at least two rows, wherein each row comprises upper conductive
- 5 segments and lower conductive segments, and in at least one row the upper conductive
- 6 segments are longer than the lower conductive segments.
- 1 29. The integrated circuit component recited in claim 28 wherein, in forming the at
- 2 least one multi-level inductive element, the upper conductive segments in one row are
- 3 offset 180 degrees from the upper conductive segments in an adjacent row.
- 1 30. The integrated circuit component recited in claim 28 wherein, in forming the at
- 2 least one multi-level inductive element, the at least one multi-level inductive element
- 3 comprises at least one layer of magnetic material.
- 1 31. An integrated circuit fabricated by:
- 2 forming at least one multi-level inductive element on a substrate in a serpentine
- 3 pattern comprising at least two rows, wherein each row comprises upper conductive

- 4 segments and lower conductive segments, and in at least one row the upper conductive
- 5 segments are longer than the lower conductive segments.
- 1 32. The integrated circuit recited in claim 31 wherein, in forming, the upper
- 2 conductive segments and the lower conductive segments are arranged in a stepped
- 3 manner.
- 1 33. The integrated circuit recited in claim 31 wherein, in forming, the upper
- 2 conductive segments and the lower conductive segments are arranged in an undulating
- 3 manner.
- 1 34. The integrated circuit recited in claim 31 wherein, in forming, the upper
- 2 conductive segments in one row are offset 180 degrees from the upper conductive
- 3 segments in an adjacent row.
- 1 35. The integrated circuit recited in claim 31 wherein, in forming, the at least one
- 2 multi-level inductive element comprises at least one layer of magnetic material.